Hyperspectral cathodoluminescence imaging of InAIN/AIGaN quantum well/quantum barrier-structures

Gunnar Kusch^{1*}; Haoning Li²; Paul R. Edwards¹; Vitaly Z. Zubialevich²; Peter J. Parbrook²; Robert W. Martin¹

¹Department of Physics, SUPA, University of Strathclyde, 107 Rottenrow East, Glasgow G4 0NG, United Kingdom ²Tyndall National Institute, University College Cork, Lee Maltings, Dyke Parade, Cork, Ireland *Gunnar.kusch@strath.ac.uk

Motivation

There are many interesting possibilities for the growth of high quality InAIN/AIGaN based semiconductor devices that have \hat{a}_{0} not been fully explored, and this remains one of the key challenges in the III-nitride material system. This is due to the complicated growth mechanics which potentially lead to phase separation and compositional inhomogeneity.



The large differences in growth temperature and lattice constant between InN and AIN present further challenges for the successful growth of InAIN/AIGaN based semiconductor devices.

MOVPE growth

- Close coupled showerhead reactor
- N_2 carrier gas was used for the quantum well structures
- Substrate: c-plane sapphire
- Precursors: TMGa, TMAI, TMIn, NH₃

Hyperspectral Cathodoluminescence

- All measurements at room temperature
- 5 kV acceleration Voltage
- ~ 150 nm penetration depth

according to Monte Carlo simulations





Performed in a FEI Quanta 250 ESEM (allowing mapping of low conductivity samples)

Measurement Setup and mode of operation for Hyperspectral CL

Variation of specific growth parameters for InAIN/AIGaN structures

1. QW growth temperature – 782 °C AIGaN NBE – 752 °C – 735 °C (a.u.) **InAIN QW** СШ 4.5 3.5 740 730 750 760 Energy (eV) Growth temp. (°C)

- Decreasing InN concentration with increasing QW growth temperature
- Emission energy between 3.55 eV (735 °C) and 3.85 eV (782 °C)
- Strong decrease in QW intensity with increasing QW growth temperature
 - \rightarrow Strong influence on intensity and wavelength









- AFM measurements on samples with a substrate miscut of 0.1°(a) and 0.4°(b)
- RMS roughness is 4 nm (a) and 5 nm (b)
- Two different morphologies
 - a) Small hillocks separated by valleys
 - b) Large surface steps





- SE-image (mag x12000) and CL maps (5x5 µm) of 752 °C and 735 °C sample
- There are few surface features/defects
- AIGaN domains with different emission energies, small variation in QW emission
 - \rightarrow Weak influence on spatial homogeneity

2. Barrier and buffer composition



- AIGaN NBE emission energy between 4.27 eV (36% AIN) and 4.92 eV (65% AIN)
- Increasing QW intensity with increasing AIN concentration
 - → Better confinement

- SE-image and CL-map for emission energy and intensity of sample a)
- AIGaN domains with varying emission energy
- Emission energy fairly constant in each domain
- Formation of domains is a possible process to reduce strain



- SE-image and CL-maps for emission energies of sample b)
- 4.54 eV peak constant over area except in regions with surface steps
- No AlGaN domains
- Surface steps correlate to 4.41 eV peak
- → Two AlGaN peaks
- → Reduced AIN incorporation along step edges
- → High miscut promotes formation of stress relieving step bunches
- → Strong influence of substrate miscut on stress relief and surface morphology

Conclusion

Growth Parameters

Strong influence of QW growth temperature on intensity and wavelength of QW emission



- Increasing AIN% \rightarrow deteriorating morphology, increasing strain \rightarrow increasing ΔE_{AIGaN} - Increasing AIN% \rightarrow increasing strain \rightarrow decreasing InAIN spatial homogeneity \rightarrow Strong influence on morphology and homogeneity

- Weak influence of growth temperature on spatial homogeneity
- AIN composition in barrier influences QW intensity
- Increase in AIN composition of buffer reduces surface morphology and spatial homogeneity

Substrate miscut

- Different miscut leads to different strain relaxation processes and thus to different morphologies

